

Subst. Form PTO-1449  <b>INFORMATION DISCLOSURE CITATION IN AN APPLICATION</b>  <i>(Use several sheets if necessary)</i>				Docket Number (Optional) <div style="border: 1px solid black; padding: 2px; text-align: center;">SAM-0483</div>		Application Number <div style="border: 1px solid black; padding: 2px; text-align: center;">10/782,094</div>	
				Applicant <div style="border: 1px solid black; padding: 2px; text-align: center;">Jae-eun Park, <i>et al.</i></div>			
				Filing Date <div style="border: 1px solid black; padding: 2px; text-align: center;">02/19/04</div>		Group Art Unit <div style="border: 1px solid black; padding: 2px; text-align: center;">2813</div>	
<b>U. S. Patent Documents</b>							
EXAMINER INITIAL	DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE	
TW	AA	6,090,442	07/18/00	Klaus, <i>et al.</i>	427	255.15	10/02/97
	AB						
	AC						
	AD						
	AE						
	AF						
	AG						
	AH						
	AI						
	AJ						
	AK						
<b>FOREIGN PATENT DOCUMENTS</b>							
	DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUBCLASS	Translation YES      NO	
	AL						
	AM						
	AN						
	AO						
	AP						
	AQ						
<b>OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)</b>							
	AR						
	AS						
	AT						
EXAMINER <div style="text-align: center; font-size: 1.5em;">T. N. B. W. P. E. N.</div>				DATE CONSIDERED <div style="text-align: center; font-size: 1.5em;">12/16/05</div>			
<b>EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP § 609; Draw line through citation if not in conformance and not considered. Include copy with next communication to applicant.</b>							



Sheet 1 of 1

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INFORMATION DISCLOSURE CITATION IN AN APPLICATION  (Use several sheets if necessary)				Applicant <b>Jae-eun Park, et al.</b>				
				Filing Date <b>02/19/04</b>		Group Art Unit <b>2813</b>		
U. S. Patent Documents								
EXAMINER INITIALS		DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE	
	AA			/				
TN	AB	5,470,800	11-28-95	Muroyama	437	238	03-26-93	
	AC	6,037,275	03-14-00	Wu, et al.	438	780	08-27-98	
	AD	6,270,572	08-07-01	Kim, et al.	117	93	08-09-99	
	AE	2002/0001974	01-03-02	Chan	438	785	06-20-01	
TN	AF	6,391,803	05-21-02	Kim, et al.	438	787	06-20-01	
	AG			/				
	AH			/				
	AI			/				
	AJ			/				
	AK			/				
FOREIGN PATENT DOCUMENTS								
		DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUBCLASS	Translation YES NO	
TN	AL	06132276	05-13-94	Japan	H01L	21/312		X
	AM	1 096 042	05-02-01	Europe	C30B	25/02		
	AN	1 003 210	05-24-00	Europe	H01L	21/316		
	AO	10189582	07-21-98	Japan	H01L	21/316		X
	AP	2001002990	01-09-01	Japan	C09D	183/04		X
TN	AQ	1 139 399	10-04-01	Europe	H01L	21/306		
OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)								
TN	AR	Klaus, J.W., et al., "Atomic layer controlled growth of SiO <sub>2</sub> films using binary reaction sequence chemistry," American Institute of Physics, 1997, Pages 1092-1094						
	AS	/						
	AT	/						
EXAMINER <b>T. NGUYEN</b>				DATE CONSIDERED <b>12/16/05</b>				
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1/3/05

# ELECTRONIC INFORMATION DISCLOSURE STATEMENT

Electronic Version v18

Stylesheet Version v18.0

## Title of Invention

Method of Forming Silicon Dioxide Using Siloxane

Application Number : 10/782094  
 Confirmation Number: 4756  
 First Named Applicant: Jae-Eun Park  
 Attorney Docket Number: SAM-0483



Art Unit:

Examiner:

Search string: ( 6664156 or 5037514 or 6534395 or 20020164890 or 20030015764 or 20020047151 ).pn

## US Patent Documents

**Note: Applicant is not required to submit a paper copy of cited US Patent Documents**

init	Cite.No.	Patent No.	Date	Patentee	Kind	Class	Subclass
TN	1	6664156	2003-12-16	Ang, et al.		—	—
TN	2	5037514	1991-08-06	Yamazaki		—	—
TN	3	6534395	2003-03-18	Werkhoven, et al.		—	—

## US Published Applications

**Note: Applicant is not required to submit a paper copy of cited US Published Applications**

init	Cite.No.	Pub. No.	Date	Applicant	Kind	Class	Subclass
TN	1	20020164890	2002-11-17	Kwan, et al.		—	—
TN	2	20030015764	2003-01-23	Raaijmakers, et al.		—	—
TN	3	20020047151	2002-04-25	Kim, et al.		—	—

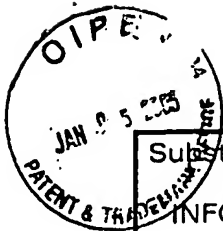
## Remarks

Note: Remarks are not for responding to an office action.

part 1 of 1

**Signature**

Examiner Name	Date
J. NEWTON	12/16/05



Sheet 1 of 1

Subst. Form PTO-1449

Docket Number (Optional)

SAM-0483

Application Number

10/782,094

INFORMATION DISCLOSURE CITATION  
IN AN APPLICATION

Applicant

Jae-eun Park, et al.

Filing Date

02/19/04

Group Art Unit

2813

(Use several sheets if necessary)

## U. S. Patent Documents

EXAMINER INITIALS		DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE
	BA						
	BB						
	BC						
	BD						
	BE						
	BF						
	BG						
	BH						
	BI						
	BJ						
	BK						

## FOREIGN PATENT DOCUMENTS

		DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUBCLASS	Translation	
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TN	BL	2002-0085487	11/16/02	Korea	H01L	21/20		X
	BM							
	BN							
	BO							
	BP							
	BQ							

## OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)

	BR	
	BS	
	BT	

EXAMINER

T. Nguyen

DATE CONSIDERED

12/16/05


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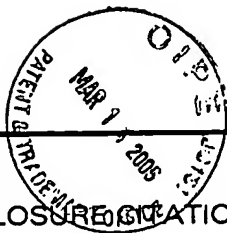
2/2/05

# ELECTRONIC INFORMATION DISCLOSURE STATEMENT

Electronic Version v18

Stylesheet Version v18.0

<b>Title of Invention</b>	Method for forming silicon dioxide film using siloxane						
Application Number :		10/782094					
Confirmation Number:		4756					
First Named Applicant:		Jae-Eun Park					
Attorney Docket Number:		SAM-0483					
Art Unit:							
Examiner:							
Search string:		( 20040096582 ).pn					
<b>US Published Applications</b>							
Note: Applicant is not required to submit a paper copy of cited US Published Applications							
init	Cite.No.	Pub. No.	Date	Applicant	Kind	Class	Subclass
TM	1	20040096582	2004-05-20	Wang, et al.			
<b>Remarks</b>							
Note: Remarks are not for responding to an office action.							
Part 1 of 1.							
<b>Signature</b>							
Examiner Name				Date			
T. N. Nguyen				12/16/05			



Sheet 1 of 2

Subst. Form PTO-1449 <b>INFORMATION DISCLOSURE CITATION IN AN APPLICATION</b> <i>(Use several sheets if necessary)</i>				Docket Number (Optional) <b>SAM-0483</b>		Application Number <b>10/782,094</b>		
				Applicant <b>Jae-eun Park, et al.</b>				
				Filing Date <b>02/19/04</b>		Group Art Unit <b>2813</b>		
<b>U. S. Patent Documents</b>								
EXAMINER INITIALS		DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE	
	AA							
	AB							
	AC							
	AD							
	AE							
	AF							
TN	AG	2002/0068466	06/06/02	Lee, et al.	438	765	05/31/01	
TN	AH	6,465,371	10/15/02	Lim	438	785	10/15/02	
	AI							
	AJ							
	AK							
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	AS							
	AT							
EXAMINER <b>T. NGUYEN</b>				DATE CONSIDERED <b>12/16/05</b>				
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Sheet 2 of 2

Subst. Form PTO-1449

Docket Number (Optional)

SAM-0483

Application Number

10/782,094

INFORMATION DISCLOSURE CITATION  
IN AN APPLICATION

Applicant

Jae-eun Park, et al.

Filing Date

02/19/04

Group Art Unit

2813

(Use several sheets if necessary)

## U. S. Patent Documents

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	BA						
	BB						
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	BF						
	BG						
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	BI						
	BJ						
	BK						

## FOREIGN PATENT DOCUMENTS

		DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUBCLASS	Translation	
							YES	NO
	BL							
TN	BM	02-2579	01/10/02	Korea	H01L	21/316		X
TN	BN	02-44422	06/15/02	Korea	H01L	21/20		X
	BO							
	BP							
	BQ							

## OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)

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	BS	
	BT	

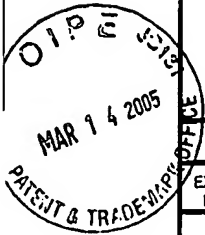
EXAMINER

T. NGUYEN

DATE CONSIDERED

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6/28/05

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Method for forming silicon dioxide film using siloxane

Application Number : 10/782094  
Confirmation Number: 4756  
First Named Applicant: Jae-eun Park  
Attorney Docket Number: SAM-0483  
Art Unit:  
Examiner:  
Search string: ( 3313792 ).pn



### US Patent Documents

Note: Applicant is not required to submit a paper copy of cited US Patent Documents

init	Cite.No.	Patent No.	Date	Patentee	Kind	Class	Subclass
JN	1	3313792	1967-04-11	Duck, et al.			

### Remarks

Note: Remarks are not for responding to an office action.

Part 1 of 1.

### Signature

Examiner Name	Date
J. N. BROWN	12/16/05